

Falcon® P-Nylon Photoresist Filter



Data Sheet MEFALNENc

Description

The Falcon P-Nylon Photoresist filter is specifically designed to filter point-of-use photoresist and developers. The naturally hydrophilic nylon 6,6 membrane, with HDPE support and hardware, allows spontaneous wettability. This minimizes photochemical waste by providing quick start up, minimal bubble generation, and consistent performance. Low pressure drop is assured by the patented crescent shaped Ultipleat® filter configuration.

Features and Benefits

- Optimized for complete and total wetting
- Low hold-up volume
- Quick venting
- Excellent compatibility
- Low differential pressure
- Low extractables
- Manufactured in a cleanroom environment
- Captured O-ring to ease filter change out
- Designed to fit most older photoresist dispense systems



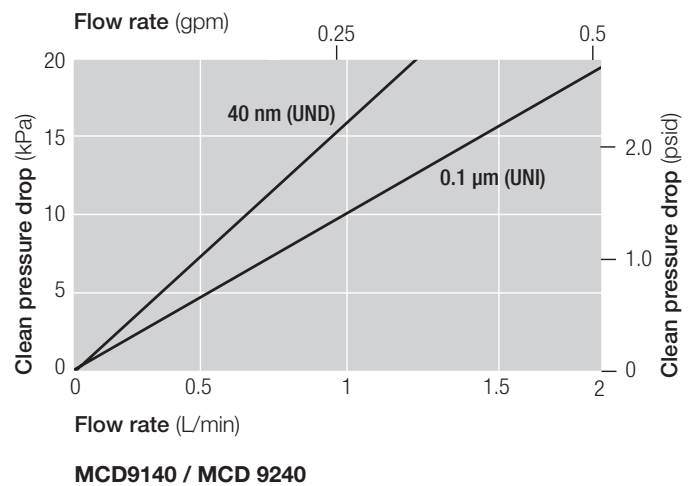
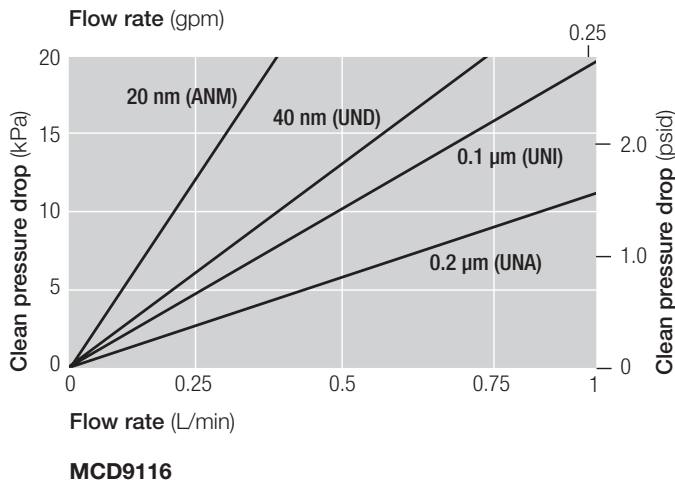
Specifications

Materials of Construction

Components	Materials
Filter Medium	Hydrophilic nylon 6,6
Core, Cage, and End Caps	High Density Polyethylene (HDPE)
Support and Drainage	High Density Polyethylene (HDPE)
O-ring Options	Fluoroelastomer, EPR, Perfluoroelastomer

Removal Ratings	0.2 µm, 0.1 µm, 40 nm, 20 nm		
Configurations	9116 Style	9140 Style	9240 Style
Filter Areas	1400 cm ² / 1.5 ft ²	3700 cm ² / 4.0 ft ²	
Nominal Length	52 mm / 2.04 in	113.5 mm / 4.47 in	127 mm / 5.02 in
Diameter	66 mm / 2.62 in		
O-ring Size / End Caps	Single 015 external / flat end		Double 118 external / flat end
Maximum Operating Temperature	60 °C / 140 °F		
Maximum Forward / Reverse Differential Pressure	410 kPa @ 50 °C / 60 psid @ 120 °F		
Recommended Applications	Up to 3% TMAH-based developers		
	i-line, 248 nm, and 193 nm photoresist		
	Anti-reflective coatings		
	Solvents		

Typical Flow Characteristics – 1 cP fluid, 20 °C



Part Numbers / Ordering Information

Part Number	Removal Rating	Nominal Length (mm / in)	O-Ring Size / Endcap	O-Ring Material
MCD9116UNAEJ	0.2 µm	52 / 2.04	015 / flat end	EPR
MCD9116UNIEJ	0.1 µm	52 / 2.04	015 / flat end	EPR
MCD9116UNIEH11	0.1 µm	52 / 2.04	015 / flat end	Perfluoroelastomer
MCD9140UNIEH	0.1 µm	113.5 / 4.47	015 / flat end	Fluoroelastomer
MCD9140UNIEJ	0.1 µm	113.5 / 4.47	015 / flat end	EPR
MCD9140UNIEH11	0.1 µm	113.5 / 4.47	015 / flat end	Perfluoroelastomer
MCD9240UNIEH11	0.1 µm	127.5 / 5.02	Double 118 / flat end	Perfluoroelastomer
MCD9116UNDEH	40 nm	52 / 2.04	015 / flat end	Fluoroelastomer
MCD9116UNDEJ	40 nm	52 / 2.04	015 / flat end	EPR
MCD9116UNDEH11	40 nm	52 / 2.04	015 / flat end	Perfluoroelastomer
MCD9140UNDEH	40 nm	113.5 / 4.47	015 / flat end	Fluoroelastomer
MCD9140UNDEJ	40 nm	113.5 / 4.47	015 / flat end	EPR
MCD9140UNDEH11	40 nm	113.5 / 4.47	015 / flat end	Perfluoroelastomer
MCD9240UNDEH11	40 nm	127.5 / 5.02	Double 118 / flat end	Perfluoroelastomer
MCD9116ANMEH11	20 nm	52 / 2.04	015 / flat end	Perfluoroelastomer



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IF APPLICABLE Please contact Pall Corporation to verify that the product conforms to your national legislation and/or regional regulatory requirements for water and food contact use.

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